2003-1126 67,200-1256

Abstract of the Disclosure

A novel method for seasoning a process chamber to substantially reduce the quantity of particulate residues remaining in the chamber after semiconductor fabrication or other processes are carried out in the chamber, is disclosed. The seasoning method includes providing a seasoning film on the interior surfaces of a process chamber, typically after cleaning of the chamber. Accordingly, the quantity of particulate byproduct residues which remain in the chamber after processing is substantially reduced.